

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	8692	430/5.ccls.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/03/08 09:51
L2	25576	(mask or photomask or reticle or \$3PSM) near4 (set or trim\$4)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/03/08 10:55
L3	21656	\$3PSM or (mask or photomask or reticle) near4 (phase or shift\$3)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/03/08 09:55
L4	7209	(mask or photomask or reticle) same (semitransparen\$3 or semi transparen\$3 or attenuate or attenuating or attenuated or semitransluscen\$3 or semitransmi\$5 or partial\$3 near2 (transparen\$3 or transmi\$5)) or attPSM	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/03/08 10:05
L5	3952	(mask or photomask or reticle or \$3PSM) same (dummy or subresolution or sub resolution or (below or smaller than or less than) near3 (resolution or resolve or resolved or resolving)) same (structure or feature or pattern or grid or grating or array or opening or hole)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/03/08 10:35
L6	97	1 and 2 and 3 and 4 and 5	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/03/08 10:16
L7	57	6 and ((alternated or alternating or Levenson or Shibuya) near2 (phas\$3 or shift\$3) near2 (mask or photomask or reticle) or altPSM or alt PSM or (alternated or alternating or Levenson or Shibuya) near2 PSM)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/03/08 10:21
L8	40	6 not 7	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/03/08 10:22
L9	45	2 and 3 and 4 and 5 and ((alternated or alternating or Levenson or Shibuya) near2 (phas\$3 or shift\$3) near2 (mask or photomask or reticle) or altPSM or alt PSM or (alternated or alternating or Levenson or Shibuya) near2 PSM) not 7 not 8	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/03/08 10:24

EAST Search History

L10	103	1 and 2 and 5 not 7 not 8 not 9	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/03/08 10:30
L11	107	1 and 3 and 4 and 5 not 7 not 8 not 9 not 10	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/03/08 10:36
L12	461	(mask or photomask or reticle or \$3PSM) same (set or trim\$4) same (dummy or subresolution or sub resolution or (below or smaller than or less than) near3 (resolution or resolve or resolved or resolving)) same (structure or feature or pattern or grid or grating or array or opening or hole)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/03/08 10:35
L13	34	1 and 12 not 7 not 8 not 9 not 10 not 11	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/03/08 10:53
L14	57	1 and 2 same 4 not 7 not 8 not 9 not 10 not 11 not 13	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/03/08 10:54
L15	2	1 and (trim\$4 or second\$3 or complement\$3 or auxilliary or additional or companion) near2 (mask or photomask or reticle or \$3PSM) same (pitch\$3 or period) same (equation or formula or expression) not 7 not 8 not 9 not 10 not 11 not 13 not 14	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/03/08 11:00
L16	9	1 and (mask or photomask or reticle or \$3PSM) same (dummy or subresolution or sub resolution or (below or smaller than or less than) near3 (resolution or resolve or resolved or resolving)) same (structure or feature or pattern or grid or grating or array or opening or hole) same (pitch\$3 or period) same (equation or formula or expression) not 7 not 8 not 9 not 10 not 11 not 13 not 14 not 15	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/03/08 11:02
L17	18	1 and (mask or photomask or reticle or \$3PSM) same (resolution or resolve or resolved or resolving) same (structure or feature or pattern or grid or grating or array or opening or hole) same (pitch\$3 or period) same (equation or formula or expression) not 7 not 8 not 9 not 10 not 11 not 13 not 14 not 15 not 16	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/03/08 11:06

EAST Search History

L18	11626	(Infineon Technologies AG).as.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/03/08 11:12
L19	28	18 and (Wolfgang near2 Dettmann or Jorg near2 Thiele or Rainer near2 Pforr or Mario near2 Hennig or Karsten Zeiler).in. not 7 not 8 not 9 not 10 not 11 not 13 not 14 not 15 not 16 not 17	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/03/08 11:17
L20	1	18 and (Roderick near2 Kohle or Rainer near2 Pforr or Jorg near2 Thiele or Wolfgang near2 Dettmann or Markus near2 Hofsass or Mario near2 Hennig).in. not 7 not 8 not 9 not 10 not 11 not 13 not 14 not 15 not 16 not 17 not 19	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/03/08 11:17
S1	3	((("6680151") or ("6730463") or ("6794095")).PN.	US-PGPUB; USPAT	OR	OFF	2007/03/06 12:28
S2	1	("20040202943").PN.	US-PGPUB; USPAT	OR	OFF	2007/03/06 12:28
S3	1	("20040197677").PN.	US-PGPUB; USPAT	OR	OFF	2007/03/06 14:02
S4	4	((("20030008219") or ("5786113") or ("5858625") or ("6680151")).PN.	US-PGPUB; USPAT	OR	OFF	2007/03/06 14:02

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L8	425	(430/5 and 430/394).ccls.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/03/08 16:25
L9	17607	(trim\$4 or set) near2 (mask or photomask or reticle or \$3PSM)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/03/08 16:26
L10	128	8 and 9	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/03/08 16:27
L11	7	10 and (subresolution or sub resolution) same (trim\$4 or set)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/03/08 16:29
L12	8692	430/5.ccls.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/03/08 16:32
L13	25576	(mask or photomask or reticle or \$3PSM) near4 (set or trim\$4)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/03/08 16:32
L14	21656	\$3PSM or (mask or photomask or reticle) near4 (phase or shift\$3)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/03/08 16:32
L15	7209	(mask or photomask or reticle) same (semitransparen\$3 or semi transparen\$3 or attenuate or attenuating or attenuated or semitransluscen\$3 or semitransmi\$5 or partial\$3 near2 (transparen\$3 or transmi\$5)) or attPSM	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/03/08 16:32
L16	3952	(mask or photomask or reticle or \$3PSM) same (dummy or subresolution or sub resolution or (below or smaller than or less than) near3 (resolution or resolve or resolved or resolving)) same (structure or feature or pattern or grid or grating or array or opening or hole)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/03/08 16:32
L17	97	L12 and L13 and L14 and L15 and L16	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/03/08 16:32

EAST Search History

L18	57	L17 and ((alternated or alternating or Levenson or Shibuya) near2 (phas\$3 or shift\$3) near2 (mask or photomask or reticle) or altPSM or alt PSM or (alternated or alternating or Levenson or Shibuya) near2 PSM)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/03/08 16:32
L19	40	L17 not L18	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/03/08 16:32
L20	45	L13 and L14 and L15 and L16 and ((alternated or alternating or Levenson or Shibuya) near2 (phas\$3 or shift\$3) near2 (mask or photomask or reticle) or altPSM or alt PSM or (alternated or alternating or Levenson or Shibuya) near2 PSM) not L18 not L19	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/03/08 16:32
L21	103	L12 and L13 and L16 not L18 not L19 not L20	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/03/08 16:32
L22	107	L12 and L14 and L15 and L16 not L18 not L19 not L20 not L21	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/03/08 16:32
L23	461	(mask or photomask or reticle or \$3PSM) same (set or trim\$4) same (dummy or subresolution or sub resolution or (below or smaller than or less than) near3 (resolution or resolve or resolved or resolving)) same (structure or feature or pattern or grid or grating or array or opening or hole)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/03/08 16:32
L24	34	L12 and L23 not L18 not L19 not L20 not L21 not L22	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/03/08 16:32
L25	57	L12 and L13 same L15 not L18 not L19 not L20 not L21 not L22 not L24	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/03/08 16:32
L26	2	L12 and (trim\$4 or second\$3 or complement\$3 or auxilliary or additional or companion) near2 (mask or photomask or reticle or \$3PSM) same (pitch\$3 or period) same (equation or formula or expression) not L18 not L19 not L20 not L21 not L22 not L24 not L25	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/03/08 16:32

EAST Search History

L27	9	L12 and (mask or photomask or reticle or \$3PSM) same (dummy or subresolution or sub resolution or (below or smaller than or less than) near3 (resolution or resolve or resolved or resolving)) same (structure or feature or pattern or grid or grating or array or opening or hole) same (pitch\$3 or period) same (equation or formula or expression) not L18 not L19 not L20 not L21 not L22 not L24 not L25 not L26	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/03/08 16:32
L28	18	L12 and (mask or photomask or reticle or \$3PSM) same (resolution or resolve or resolved or resolving) same (structure or feature or pattern or grid or grating or array or opening or hole) same (pitch\$3 or period) same (equation or formula or expression) not L18 not L19 not L20 not L21 not L22 not L24 not L25 not L26 not L27	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/03/08 16:32
L29	92	10 not 11 not L18 not L19 not L20 not L21 not L22 not L24 not L25 not L26 not L27 not L28	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/03/08 16:34